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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/581,669	06/05/2006	Akihisa Hongo	2006-0835A	4575
513 7590 08/28/2009 WENDEROTH, LIND & PONACK, L.L.P. 1030 15th Street, N.W., Suite 400 East Washington, DC 20005-1503			EXAMINER	
			MORGAN, EILEEN P	
			ART UNIT	PAPER NUMBER
_			3723	
			MAIL DATE	DELIVERY MODE
			08/28/2009	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

	Application No.	Applicant(s)			
	10/581,669	HONGO ET AL.			
Office Action Summary	Examiner	Art Unit			
	Eileen P. Morgan	3723			
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address			
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be tim vill apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	l. lely filed the mailing date of this communication. (35 U.S.C. § 133).			
Status					
Responsive to communication(s) filed on 23 Ju This action is FINAL . 2b) ☑ This Since this application is in condition for allowar closed in accordance with the practice under E	action is non-final. nce except for formal matters, pro				
Disposition of Claims					
4) ☐ Claim(s) 1-20 is/are pending in the application. 4a) Of the above claim(s) 1-10 and 17-20 is/are 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 11-16 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or Application Papers 9) ☐ The specification is objected to by the Examine 10) ☐ The drawing(s) filed on is/are: a) ☐ access applicant may not request that any objection to the original part of the content	e withdrawn from consideration. r election requirement. r. epted or b) objected to by the E				
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).					
11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.					
Priority under 35 U.S.C. § 119					
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 					
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO/SB/08) Paper No(s)/Mail Date 6-5-06.	4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:	te			

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DETAILED ACTION

Claim Rejections - 35 USC § 112

The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

Claims 11-16 rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

Claim 1, how does a polishing unit have a chamber 'therein'? Isn't the unit the actually polishing machine? Is the unit inside the chamber? Claim 14, what is the difference between the polishing unit and polishing area? Is the partition part of the chamber? Is the polishing area the same as the chamber? The cleaning unit and cleaning area? Where are these 'areas' relative to the units? The chamber? Is the internal pressure different fro the chamber?

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 11-16 rejected under 35 U.S.C. 103(a) as being unpatentable over Nishi et al.-6,500,051 in view of Hasegawa et al.-5,733,181.

Nishi discloses the claimed invention including a substrate processing apparatus having: a polishing unit (2) having a CMP surface polisher (7) within a

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chamber (48), a cleaning unit (30) within a chamber (49) and a drying unit (col. 3, line 17; col. 5, line 41), the chambers divided by a wall (22), the internal pressure in polishing chamber lower than the cleaning pressure (col. 2, line 63), the cleaning chamber having a fan (101). Nishi does not disclose using a tape polisher for polishing a bevel edge or notch in substrate periphery. However, a notch/edge bevel polishing unit (col.4, line 15) is taught by Hasegawa that uses a polishing tape in sliding contact with edge or notch portion. This type of polisher is well-known in the wafer edge/notch polishing art and to include a tape polisher for notch/edge polishing, as taught by Hasegawa, within the polishing chamber as disclosed by Nishi, would have been obvious to one of ordinary skill in the art at time invention was made in order to be able to thoroughly polish wafer edges and notches.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Eileen P. Morgan whose telephone number is 571.272.4488. The examiner can normally be reached on Monday-Thursday, 7am-3:30pm EST.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Joseph Hail can be reached on 571.272.4485. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

EM August 27, 2009

/Eileen P Morgan/ Primary Examiner, Art Unit 3723